



SFW

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Jun HATAKEYAMA et al.

Group Art Unit: 1752

Application No.: 10/797,201

Examiner: R. SCHILLING

Filed: March 11, 2004

Docket No.: 118988

For: AN ANTI-REFLECTION FILM MATERIAL AND A SUBSTRATE HAVING AN
ANTI-REFLECTION FILM AND A METHOD FOR FORMING A PATTERN

AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In reply to the February 21, 2006, Office Action, please consider the following:

Amendments to the Claims as reflected in the listing of claims; and

Remarks.